Measurement of: Fabrication of micron sized patterns using Ar ion milling

Equipment: Argon Ion Milling Facility

Property Measured: Fabrication of micron sized patterns using Ar ion milling

Photograph (small size)

Basic Principle: This facility is used for fabrication of micron sized patterns using Ar ion. It includes turbo pumping station for a clean and oil free operation, rotating sample stage with water cooling arrangement for uniform milling, gridded ion source with filament neutralizer,4 inch diameter collimated ion beam with 120 mA beam current and 100 – 1200 operating voltage range.

Capabilities: Down to 10 micron feature size can be realized

Sample Requirement: Thin film samples